

**ANALOG VLSI DESIGN
(ECEN 4145)**

Time Allotted : 2½ hrs

Full Marks : 60

Figures out of the right margin indicate full marks.

*Candidates are required to answer Group A and
any 4 (four) from Group B to E, taking one from each group.*

Candidates are required to give answer in their own words as far as practicable.

Group – A

1. Answer any twelve:

12 × 1 = 12

Choose the correct alternative for the following

- (i) For push-pull amplifier operation
 - (a) NMOS will be in saturation, PMOS will be in linear mode
 - (b) NMOS will be in linear, PMOS will be in saturation mode
 - (c) Both NMOS and PMOS will be in saturation mode
 - (d) Both NMOS and PMOS will be in linear mode.
- (ii) An ideal differential amplifier amplifier should have CMRR
 - (a) $0 < CMRR < 1$
 - (b) 1
 - (c) Infinite
 - (d) Zero.
- (iii) If the substrate terminals of the transistors forming the source-coupled pair of the CMOS differential amplifier is connected to ground then,
 - (a) Threshold voltages depend on C_{bd} and C_{bs}
 - (b) Threshold voltages decrease nonlinearly
 - (c) Threshold voltages decrease linearly
 - (d) Threshold voltages increase.
- (iv) Practical current mirror circuits deviate from the ideal behaviour due to
 - (a) Channel length modulation effect
 - (b) Threshold voltage offset between two transistors
 - (c) Imperfect geometrical matching
 - (d) all of the above.
- (v) Linear Region of Ideal MOS Transistor can be modelled as
 - (a) Capacitance
 - (b) Resistance
 - (c) Voltage Source
 - (d) Current Source.
- (vi) Most Popular Scaling Technique in Today's Nano Technology is
 - (a) Constant Voltage Scaling
 - (b) Constant Energy Scaling
 - (c) Constant Charge Scaling
 - (d) Constant Field Scaling.

- (vii) A MOSFET is ensured to operate in saturation region when
 (a) Gate-source shorted (b) Gate-substrate shorted
 (c) Source-substrate shorted (d) Gate-drain shorted.
- (viii) 3D Transistor is created using below Fabrication Process
 (a) FINFET (b) SOI
 (c) NMOS Bulk CMOS (d) PMOS Bulk CMOS.
- (ix) The frequency of the signal applied to the switched-capacitor circuit should satisfy the criteria
 (a) $f_{signal} \ll f_{clock}$ (b) $f_{signal} \gg f_{clock}$
 (c) $f_{signal} = 2f_{clock}$ (d) $f_{signal} = 0.5f_{clock}$.
- (x) 0.7 Technology Scaling enables Layout area scaling of
 (a) 0.49 (b) 1.0 (c) 1.42 (d) 0.65.

Fill in the blanks with the correct word

- (xi) Full Form of PTAT is _____.
- (xii) Full Form of SOI is _____.
- (xiii) The process of pattern transfer through mask is known as _____.
- (xiv) One of the limitations of the MOS switch is given by _____ injection.
- (xv) For the n-channel enhancement type MOSFET, the substrate terminal is connected to the most _____ potential.

Group - B

2. (a) Briefly explain the “channel formation” in n-channel enhancement-type MOSFET with necessary diagram. [[CO1](Understand/LOCQ)]
- (b) An ideal n-channel MOSFET has the following parameters:
 $L = 1.3\mu\text{m}$; $\mu_n = 660\text{cm}^2/\text{V.s}$; $C_{OX} = 7 \times 10^{-8} \text{ F}/\text{Cm}^2$; $V_T = 0.66\text{V}$; What should be the channel width (W) such that $I_{D(sat)} = 5\text{mA}$ for $V_{GS} = 5\text{V}$? [[CO1](Evaluate/HOCQ)]
- (c) Do you find the supply voltage of $+1.8\text{V}$ to be suitable for both 180nm and 45nm technology node? Justify your answer. [[CO2](Apply/IOCQ)]
4 + 5 + 3 = 12
3. (a) Briefly explain the short-channel effects in MOS structure. [[CO2](Understand/LOCQ)]
- (b) Derive the expression of drain current in MOS device and draw the characteristics curve. [[CO1](Apply/IOCQ)]
- (c) Distinguish between the transfer characteristics of depletion-type and enhancement-type MOSFET. [[CO1](Apply/IOCQ)]
5 + 4 + 3 = 12

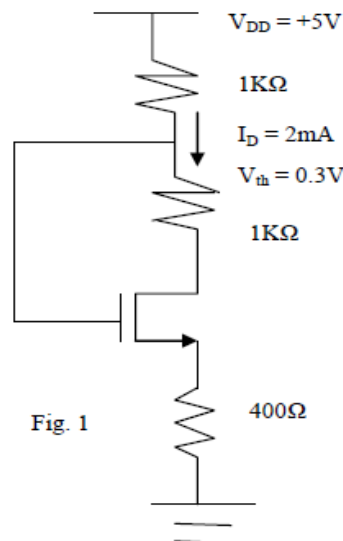
Group - C

4. (a) How you will use Photo Lithography using Negative Photo-resist to create N+ Diffusion in a P Type Substrate? [[CO3](Analyze/IOCQ)]

- (b) Explain the difference between Wet Oxidation Dry Oxidation. [[CO3](Analyze/IOCQ)]
- (c) Explain the difference between Lambda and Micron Rules. [[CO3](Analyze/IOCQ)]
- 6 + 3 + 3 = 12**
5. (a) Explain CMOS Fabrication flow step by step using self aligned N-Well Process Techniques. [[CO3](Analyze/IOCQ)]
- (b) Explain Structure of FINFET Transistor. [[CO3](Analyze/IOCQ)]
- (c) Explain Common Centroid Layout using an example. [[CO3](Analyze/IOCQ)]
- 6 + 3 + 3 = 12**

Group - D

6. (a) Briefly explain the operation of MOS as a switch. [[CO4](Understand/LOCQ)]
- (b) Can a “Dummy Transistor” help in charge injection cancellation? Justify your answer including the reason behind the name “dummy”. [[CO4](Apply/IOCQ)]
- (c) Determine the region of operation of the MOSFET in Fig. 1 and write the relevant expression of channel resistance. [[CO4](Apply/IOCQ)]



4 + 3 + 5 = 12

7. (a) Explain Small Signal low frequency model for NMOS. [[CO4](Analyze/IOCQ)]
- (b) Evaluate how Diode AC resistance is dependent on NMOS transconductance when the NMOS is used as diode. [[CO4](Evaluate/HOCQ)]
- (c) Evaluate how $V_{DD}/2$ can be realized using NMOS based Supply Voltage (V_{DD}) Divider Circuit. [[CO4](Evaluate/HOCQ)]

4 + 4 + 4 = 12

Group - E

8. (a) Evaluate how Basic Current Mirror Circuit can be Designed as Current Multiplier where $I_{out}/I_{in} = 4$. [[CO4](Evaluate/HOCQ)]
- (b) Evaluate how Cascode Current Sink can increase Output Resistance. [[CO4](Evaluate/HOCQ)]
- (c) Explain CMOS bandgap reference circuit. [[CO4](Analyze/IOCQ)]

4 + 4 + 4 = 12

9. (a) Mention the few disadvantages of the switched-capacitor circuits. [[CO6](Remember/LOCQ)]
- (b) Emulate the resistor equivalent of series-parallel switched-capacitor circuit. [[CO6](Apply/IOCQ)]
- (c) Analyze the accuracy of the switched-capacitor circuits. [[CO6](Analyze/IOCQ)]
- 4 + 5 + 3 = 12**
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Cognition Level	LOCQ	IOCQ	HOCQ
Percentage distribution	17.71	60.42	21.87

Course Outcome (CO):

After the completion of the course students will be able to

- ECEN4145.1. Understand the fundamentals of MOSFET device physics
- ECEN4145.2. Correlate the fundamental understanding with the evolving VLSI design trends and challenges
- ECEN4145.3. Understand the IC fabrication process flow leading to the practical realization of the scaled MOSFETs
- ECEN4145.4. Analyze MOS-based analog VLSI sub-circuits and design them, namely, current mirrors, voltage & current references.
- ECEN4145.5. Design MOS circuits of practical importance e.g. common-source amplifiers and differential amplifiers.
- ECEN4145.6. Understand and apply the knowledge of analog sampled data circuits to synthesize practical circuits such as switched-capacitor filters.

**LOCQ: Lower Order Cognitive Question; IOCQ: Intermediate Order Cognitive Question; HOCQ: Higher Order Cognitive Question.*